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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: Hideomi KOINUMA et al.

Application Number: Not yet assigned

Filed: September 22, 2006

For: FLUX ASSISTED SOLID PHASE EPITAXY

Attorney Docket Number: 063060

Customer Number: 38834

September 22, 2006

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450

Alexandria, VA 22313-1450

Sir:

In compliance with 37 C.F.R. §1.56, Applicants direct the attention of the Patent and

Trademark Office to the documents listed on the attached PTO/SB/08. A copy of each non- U.S. document is enclosed herewith.

If there are any fees due in connection with the filing of this paper, please charge Deposit Account No. 50-2866.

Respectfully submitted,

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SMD/ct

Enclosure: PTO/SB/08, 9 documents and Int'l Search Report

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Combined Form PTO/SB/08A&B				Complete if Known			
Combined Form F1O/Sb/00A	œb			Application Number	New Application		
INFORMA	ATION DISC	LOSU	<u>RE</u>	Confirmation Number			
- STATEMENT BY APPLICANT				Filing Date	September 22, 2006		
				First Named Inventor	Hideomi KOINUMA et al.		
(use as m	any sheets as ne	cessary)		Art Unit			
	•			Examiner Name			
Sheet	1	of	1	Attorney Docket Number	063060		

U.S. PATENT DOCUMENTS						
Examiner	Cite	Document Number		Publication Date		
Initials*	No.1	Number	Kind Code ² (if known)	MM-DD-YYYY	Name of Patentee or Applicant of Cited Documer	
		US				
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FOREIGN PATENT DOCUMENTS							
Examiner	Cite	Foreign Patent Document			Publication Date	Name of Patentee or	
Initials*	No.1	Country Code ³	Number ⁴	Kind Code ⁵ (if known)	MM-DD-YYYY	Applicant of Cited Document	Translation ⁶
/RK/	1	лР	2-64098	Α	03-05-1990	NEC CORP	Abstract, cited in ISR
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/RK/	6	JР	2005-1987	А	01-06-2005	Japan Science & Technology Agency	Abstract, cited in ISR

NON PATENT LITERATURE DOCUMENTS					
Examiner Initials*	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (wben appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city, and/or country where published.	Translation		
/RK/	7	Takeshi KIJIMA et al., "New Low-Temperature Processing of Metalorganic Chemical Vapor Deposition-Bi ₃ Ti ₃ O ₁₂ Thin Films Using BiOx Buffer Layer", Jpn. J. Appl. Phys. Vol. 38 (1999) pp. 127-130.	Yes		
/RK/	8	X.Q. PAN et al., "Domain structure of epitaxial Bi ₄ Ti ₃ O ₁₂ thin films grown on (001) SrTiO ₃ substrates", APPLIED PHYSICS LETTERS Vol. 83, No. 12, 22 September 2003, pp. 2315-2317.	Yes		
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1	/Robert Kunemund/	05/08/2008				
	Examiner Signature	Date Considered				
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